REMARKS

Claims 1-25 are all the claims pending in the application.

I. Formal Matters - Claim 19

In the Amendment dated August 23, 2002, it appears that Applicants' representative inadvertently left structural formula (pVI) out of the amendment to claim 19. Claim 19 is amended herein to insert the missing structural formula (pVI).

II. The Allowable Subject Matter

The Examiner has not included claims 4, 12 and 21 in the rejection. Further, on the Office Action cover page, the Examiner indicates that claims 4, 12 and 21 are "objected to."

The Examiner is requested to clarify that claims 4, 12 and 21 are allowable, but objected to as being dependent from rejected base claims.

III. The Rejection Based on Nozaki et al

Claims 1-3, 5-11, 13-20 and 22-25 are rejected under 35 U.S.C. §102(e) as allegedly being anticipated by Nozaki et al.

The Examiner considers Nozaki et al to disclose photoresist compositions containing resins that are within the scope of Applicants' claimed resins. The Examiner particularly notes Examples 3, 4, 8, 13-16 and 66-68, which the Examiner alleges disclose a copolymer comprising mevalonic lactone and an alicyclic containing methacrylate or an adamantyl methacrylate derivative.

Applicants respectfully submit that the present invention is not anticipated by the disclosures of Nozaki et al and request that the Examiner reconsider and withdraw this rejection in view of the following remarks.

Applicants respectfully submit that the resins of Nozaki et al are not within the scope of the resins of the present invention. The resins of the present invention are characterized in the position of the substituent on the lactone of the formula (I).

Formula (I) of the present invention recites that a substituent is introduced into each of R_6 and R_7 of the formula (I) in the present invention. The mevalonic lactone structure in Nozaki et al is represented in formula (XLIII) of column 31, in which a methyl group is introduced into the position corresponding to R_1 in the formula (I) of the present invention. Another structure in Nozaki et al is represented in Example 66 of column 71, in which a methyl group is introduced into each of the positions corresponding to R_4 and R_5 in formula (I) of the present invention. Each of said two compounds of Nozaki et al do not have a substituent in the position corresponding to R_6 and R_7 of the formula (I) in the present invention. Accordingly, Applicants respectfully submit that Nozaki et al does not teach or disclose Applicants' claimed invention.

For the above reasons, it is respectfully submitted that the subject matter of claims 1-3, 5-11, 13-20 and 22-25 is neither taught by nor made obvious from the

AMENDMENT UNDER 37 C.F.R. § 1.111

U.S. Appln. No. 09/620,708

disclosures of Nozaki et al and it is requested that the rejection under 35 U.S.C.

§102 be reconsidered and withdrawn.

Conclusion IV.

In view of the above, Applicants respectfully submit that their claimed

invention is allowable and ask that the rejection under 35 U.S.C. §102 be

reconsidered and withdrawn. Applicants respectfully submit that this case is in

condition for allowance and allowance is respectfully solicited.

If any points remain at issue which the Examiner feels may be best resolved

through a personal or telephone interview, the Examiner is kindly requested to

contact the undersigned at the local exchange number listed below.

Applicants hereby petition for any extension of time which may be required

to maintain the pendency of this case. The USPTO is directed and authorized to

charge all required fees, except for the Issue Fee and the Publication Fee, to Deposit

Account No. 19-4880. Please also credit any overpayments to said Deposit Account.

Respectfully submitted,

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23373 PATENT TRADEMARK OFFICE

Date: March 5, 2003

6

AMENDMENT UNDER 37 C.F.R. § 1.111 U.S. Appln. No. 09/620,708



The claim 19 is amended as follows:

19 (twice Amended). The positive photoresist composition for far ultraviolet exposure as claimed in claim 18, wherein the resin (B) further contains a repeating unit having an alkali-soluble group protected by at least one group containing an alicyclic hydrocarbon structure represented by the following formula (pI), (pII), (pIV), (pV) or (pVI):

$$\begin{array}{c}
R_{12} \\
----R_{13} \\
R_{14}
\end{array} (pII)$$

$$\begin{array}{c}
R_{17} \\
R_{19} \\
R_{20} \\
R_{21}
\end{array}$$
(pIV)

AMENDMENT UNDER 37 C.F.R. § 1.111 U.S. Appln. No. 09/620,708

wherein R_{11} represents a methyl group, an ethyl group, an n-propyl group, an isopropyl group, an n-butyl group, an isobutyl group or a sec-butyl group; Z represents an atomic group necessary for forming an alicyclic hydrocarbon group together with the carbon atom; R_{12} to R_{16} each independently represents a linear or branched alkyl group having from 1 to 4 carbon atoms or an alicyclic hydrocarbon group, provided that at least one of R_{12} to R_{14} or either one of R_{15} and R_{16} represents an alicyclic hydrocarbon group; R_{17} to R_{21} each independently represents hydrogen atom, a linear or branched alkyl group having from 1 to 4 carbon atoms or an alicyclic hydrocarbon group, provided that at least one of R_{17} to R_{21} represents an alicyclic hydrocarbon group, provided that at least one of R_{19} and R_{21} represents a linear or

AMENDMENT UNDER 37 C.F.R. § 1.111 U.S. Appln. No. 09/620,708

branched alkyl group having from 1 to 4 carbon atoms or an alicyclic hydrocarbon group; and R_{22} to R_{25} each independently represents a linear or branched alkyl group having from 1 to 4 carbon atoms or an alicyclic hydrocarbon group, provided that at least one of R_{22} to R_{25} represents an alicyclic hydrocarbon group.

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